

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:) Attorney Docket No.
	FIS920030377US1
) Confirmation No. 6138
Huang et al.)
)
Serial No.: 10/716,785) Examiner: Sin J. Lee
Filed: November 19, 2003) Group Art Unit: 1752
For: SILICON-CONTAINING RESIST)	
SYSTEMS WITH CYCLIC KETAL)	
PROTECTING GROUPS)	
) Date: April 28, 2006

The Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed Form PTO-1449. Copies of the listed documents are also enclosed.

In accordance with 37 C.F.R. § 1.98(a)(2)(iii), a copy of the non-patent publication is attached.

The Commissioner is authorized to charge to Deposit Account No. 09-0458 the amount to cover the fee under 37 C.F.R. § 1.17(p). Any additional fees due or overpayments should also be charged or credited to Deposit Account No. 09-0458.

CONCLUSION

Application No. 10/716,785

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants' undersigned attorney may be reached by telephone at (845) 894-6919. All correspondence should continue to be directed to the address listed below.

Respectfully submitted,
/Todd M. C. Li/
Todd M. C. Li
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INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) FIS920030377US1		Application Number 10/716,785		
				Applicant(s) Huang, et al.				
				Filing Date 11/19/2003		Group Art Unit 1752		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		US 5,712,078	01/27/1998	Huang, et al.				
		US 5,919,597	07/06/1999	Sinta, et al.				
U.S. PATENT APPLICATION PUBLICATIONS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
		Schmaljohann, et al - "Design Strategies for 157 nm Single-Layer Photoresists: Lithographic Evaluation of a Poly (a-trifluoromethyl vinyl alcohol) Copolymer Department of Material Science and Engineering, Cornell University In advances in Resist Technology and Processing XVII, Francis M. Houlihan, Editor Proceedings of SPIE Vol. 3999 (2000)						
EXAMINER				DATE CONSIDERED				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								